

# Christopher K Ober

## List of Publications by Year in descending order

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547  
papers

29,731  
citations

7251

80  
h-index

7627

156  
g-index

593  
all docs

593  
docs citations

593  
times ranked

28717  
citing authors

#	ARTICLE	IF	CITATIONS
1	Polymer-grafted Nanoparticles (PGNs) with Adjustable Graft Density and Interparticle Hydrogen Bonding Interaction. <i>Macromolecular Rapid Communications</i> , 2022, 43, e2100629.	2.0	3
2	Effect of monomer hydrophilicity on ATRP kinetics in aqueous mini-emulsion polymerization. <i>Journal of Polymer Science</i> , 2022, 60, 666-673.	2.0	4
3	Effects of Amphiphilic Polypeptoid Side Chains on Polymer Surface Chemistry and Hydrophilicity. <i>ACS Applied Materials &amp; Interfaces</i> , 2022, 14, 7340-7349.	4.0	5
4	Influence of spin casting solvent on the self-assembly of silicon-containing block copolymer thin films via high temperature thermal treatment. <i>Polymer International</i> , 2022, 71, 426-435.	1.6	3
5	Real time quantification of mixed ion and electron transfer associated with the doping of poly(3-hexylthiophene). <i>Journal of Materials Chemistry C</i> , 2022, 10, 7251-7262.	2.7	5
6	Investigation of N-Substituted Morpholine Structures in an Amphiphilic PDMS-Based Antifouling and Fouling-Release Coating. <i>Biomacromolecules</i> , 2022, 23, 2697-2712.	2.6	12
7	High-Performance Chain Scissionable Resists for Extreme Ultraviolet Lithography: Discovery of the Photoacid Generator Structure and Mechanism. <i>Chemistry of Materials</i> , 2022, 34, 6170-6181.	3.2	11
8	Strong Polyelectrolyte Brushes via Alternating Copolymers of Styrene and Maleimides: Synthesis, Properties, and Stability. <i>Macromolecules</i> , 2022, 55, 5291-5300.	2.2	8
9	High-Resolution Nanopatterning of Free-Standing, Self-Supported Helical Polypeptide Rod Brushes via Electron Beam Lithography. <i>ACS Macro Letters</i> , 2021, 10, 755-759.	2.3	4
10	Amphiphilic Nitroxide-Bearing Siloxane-Based Block Copolymer Coatings for Enhanced Marine Fouling Release. <i>ACS Applied Materials &amp; Interfaces</i> , 2021, 13, 28790-28801.	4.0	17
11	Using Liquid Crystals to Probe the Organization of Helical Polypeptide Brushes Induced by Solvent Pretreatment. <i>Macromolecules</i> , 2021, 54, 7786-7795.	2.2	4
12	Ionic Dopant-Induced Ordering Enhances the Thermoelectric Properties of a Polythiophene-Based Block Copolymer. <i>Advanced Functional Materials</i> , 2021, 31, 2106991.	7.8	5
13	New Approaches to EUV Photoresists: Studies of Polyacetals and Polypeptoids to Expand the Photopolymer Toolbox. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2021, 34, 71-74.	0.1	5
14	Silica-PMMA hairy nanoparticles prepared via phase transfer-assisted aqueous miniemulsion atom transfer radical polymerization. <i>Journal of Polymer Science</i> , 2020, 58, 2310-2316.	2.0	4
15	Quantifying internal charge transfer and mixed ion-electron transfer in conjugated radical polymers. <i>Chemical Science</i> , 2020, 11, 9962-9970.	3.7	13
16	Materials systems for 2-photon lithography. , 2020, , 143-174.		1
17	Thermal Stability of $\pi$ -Conjugated <i>n</i> -Ethylene-Glycol-Terminated Quaterthiophene Oligomers: A Computational and Experimental Study. <i>ACS Macro Letters</i> , 2020, 9, 295-300.	2.3	2
18	Terminology of polymers in advanced lithography (IUPAC Recommendations 2020). <i>Pure and Applied Chemistry</i> , 2020, 92, 1861-1891.	0.9	2

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19	Block copolymers containing stable radical and fluorinated blocks with long-range ordered morphologies prepared by anionic polymerization. <i>Polymer Chemistry</i> , 2019, 10, 5094-5102.	1.9	8
20	Chemical reaction and diffusion kinetics during laser-induced submillisecond heating for lithographic applications. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019, 37, 041601.	0.6	2
21	Three-Dimensional Printing of Hierarchical Porous Architectures. <i>Chemistry of Materials</i> , 2019, 31, 10017-10022.	3.2	18
22	Aqueous one-pot synthesis of epoxy-functional diblock copolymer worms from a single monomer: new anisotropic scaffolds for potential charge storage applications. <i>Polymer Chemistry</i> , 2019, 10, 194-200.	1.9	35
23	The Role of Hydrogen Bonding in Peptoid-Based Marine Antifouling Coatings. <i>Macromolecules</i> , 2019, 52, 1287-1295.	2.2	41
24	Structure Control of a $\pi$ -Conjugated Oligothiophene-Based Liquid Crystal for Enhanced Mixed Ion/Electron Transport Characteristics. <i>ACS Nano</i> , 2019, 13, 7665-7675.	7.3	29
25	Polymer-Based Marine Antifouling and Fouling Release Surfaces: Strategies for Synthesis and Modification. <i>Annual Review of Chemical and Biomolecular Engineering</i> , 2019, 10, 241-264.	3.3	118
26	Polymer Brushes: Polymer Brushes on Hexagonal Boron Nitride (Small 19/2019). <i>Small</i> , 2019, 15, 1970099.	5.2	2
27	Entropic death of nonpatterned and nanopatterned polyelectrolyte brushes. <i>Journal of Polymer Science Part A</i> , 2019, 57, 1283-1295.	2.5	7
28	Spatially Controlled Transience of Graphene-Polymer Electronics with Silicon Singulation. <i>Advanced Functional Materials</i> , 2019, 29, 1900592.	7.8	2
29	Polymer Brushes on Hexagonal Boron Nitride. <i>Small</i> , 2019, 15, 1805228.	5.2	18
30	Metal Organic Cluster Photoresists for EUV Lithography. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2019, 32, 711-714.	0.1	3
31	Stability and microbial toxicity of $\text{HfO}_2$ and $\text{ZrO}_2$ nanoparticles for photolithography. <i>Green Materials</i> , 2019, 7, 109-117.	1.1	3
32	Self-Assembly Behavior of an Oligothiophene-Based Conjugated Liquid Crystal and Its Implication for Ionic Conductivity Characteristics. <i>Advanced Functional Materials</i> , 2019, 29, 1805220.	7.8	20
33	Radical sensitive Zinc-based nanoparticle EUV photoresists. , 2019, , .		3
34	Development of metal organic cluster EUV photoresists. , 2019, , .		1
35	Metal organic cluster photoresists: new metal oxide systems. , 2019, , .		0
36	Flexible Hydrophobic Antifouling Coating with Oriented Nanotopography and Nonleaking Capsaicin. <i>ACS Applied Materials &amp; Interfaces</i> , 2018, 10, 9718-9726.	4.0	45

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37	Mini Monomer Encapsulated Emulsion Polymerization of PMMA Using Aqueous ARGET ATRP. ACS Macro Letters, 2018, 7, 459-463.	2.3	23
38	In pursuit of Moore's Law: polymer chemistry in action. Polymer Journal, 2018, 50, 45-55.	1.3	17
39	Biologically Complex Planar Cell Plasma Membranes Supported on Polyelectrolyte Cushions Enhance Transmembrane Protein Mobility and Retain Native Orientation. Langmuir, 2018, 34, 1061-1072.	1.6	35
40	Impact of the synthesis method on the solid-state charge transport of radical polymers. Journal of Materials Chemistry C, 2018, 6, 111-118.	2.7	48
41	Facile Preparation of Epoxide-Functionalized Surfaces via Photocurable Copolymer Coatings and Subsequent Immobilization of Iminodiacetic Acids. ACS Applied Materials & Interfaces, 2018, 10, 40871-40879.	4.0	18
42	Progress in metal organic cluster EUV photoresists. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2018, 36, .	0.6	7
43	Materials Overview for 2-Photon 3D Printing Applications. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 425-429.	0.1	2
44	The Challenges of Highly Sensitive EUV Photoresists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 261-265.	0.1	8
45	Synthesis, Processing, and Characterization of Helical Polypeptide Rod-Coil Mixed Brushes. ACS Macro Letters, 2018, 7, 1186-1191.	2.3	7
46	Charge Transport in Conjugated Polymers with Pendent Stable Radical Groups. Chemistry of Materials, 2018, 30, 4799-4807.	3.2	33
47	Electroluminescence from Solution-Processed Pinhole-Free Nanometer-Thickness Layers of Conjugated Polymers. Nano Letters, 2018, 18, 5382-5388.	4.5	4
48	UV-Triggered Transient Electrospun Poly(propylene carbonate)/Poly(phthalaldehyde) Polymer Blend Fiber Mats. ACS Applied Materials & Interfaces, 2018, 10, 28928-28935.	4.0	6
49	Engineered nanomaterials and human health: Part 1. Preparation, functionalization and characterization (IUPAC Technical Report). Pure and Applied Chemistry, 2018, 90, 1283-1324.	0.9	41
50	Engineered nanomaterials and human health: Part 2. Applications and nanotoxicology (IUPAC Technical Report). Pure and Applied Chemistry, 2018, 90, 1325-1374.	0.9	27
51	Metal-Organic Framework-Inspired Metal-Containing Clusters for High-Resolution Patterning. Chemistry of Materials, 2018, 30, 4124-4133.	3.2	65
52	EUV photolithography: resist progress in metal-organic complex photoresists. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2018, 18, 1.	1.0	17
53	Patterning mechanism of metal based hybrid EUV resists. , 2018, , .		1
54	EUV photolithography: resist progress and challenges. , 2018, , .		9

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55	EUV metal oxide hybrid photoresists: ultra-small structures for high-resolution patterning. , 2018, , .		2
56	Fifty years of the Baier curve: progress in understanding antifouling coatings. <i>Green Materials</i> , 2017, 5, 1-3.	1.1	16
57	Model Amphiphilic Block Copolymers with Tailored Molecular Weight and Composition in PDMS-Based Films to Limit Soft Biofouling. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 16505-16516.	4.0	30
58	<i>50th Anniversary Perspective</i>: Polymer Brushes: Novel Surfaces for Future Materials. <i>Macromolecules</i> , 2017, 50, 4089-4113.	2.2	393
59	Transient Fiber Mats of Electrospun Poly(Propylene Carbonate) Composites with Remarkable Mechanical Strength. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 25495-25505.	4.0	12
60	Morphology of Nanostructured Polymer Brushes Dependent on Production and Treatment. <i>Macromolecules</i> , 2017, 50, 4715-4724.	2.2	12
61	Ultrafast Self-Assembly of Sub-10 nm Block Copolymer Nanostructures by Solvent-Free High-Temperature Laser Annealing. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 31317-31324.	4.0	33
62	Role of Backbone Chemistry and Monomer Sequence in Amphiphilic Oligopeptide- and Oligopeptoid-Functionalized PDMS- and PEO-Based Block Copolymers for Marine Antifouling and Fouling Release Coatings. <i>Macromolecules</i> , 2017, 50, 2656-2667.	2.2	66
63	A dress code for block copolymers. <i>Nature Nanotechnology</i> , 2017, 12, 507-508.	15.6	7
64	Nanoparticle photoresist studies for EUV lithography. <i>Proceedings of SPIE</i> , 2017, , .	0.8	19
65	Perpendicular Orientation Control without Interfacial Treatment of RAFT-Synthesized High- $\chi$ Block Copolymer Thin Films with Sub-10 nm Features Prepared via Thermal Annealing. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 31266-31278.	4.0	57
66	Reduced Lateral Confinement and Its Effect on Stability in Patterned Strong Polyelectrolyte Brushes. <i>Langmuir</i> , 2017, 33, 3296-3303.	1.6	16
67	Oligopeptide-modified hydrophobic and hydrophilic polymers as antifouling coatings. <i>Green Materials</i> , 2017, 5, 31-43.	1.1	9
68	Manipulation of cell adhesion and dynamics using RGD functionalized polymers. <i>Journal of Materials Chemistry B</i> , 2017, 5, 6307-6316.	2.9	34
69	Correction: Manipulation of cell adhesion and dynamics using RGD functionalized polymers. <i>Journal of Materials Chemistry B</i> , 2017, 5, 6973-6973.	2.9	1
70	Lithography performance and environmental compatibility of PFOS-free photoacid generators. <i>Green Materials</i> , 2017, 5, 173-181.	1.1	2
71	MEMS analogous micro-patterning of thermotropic nematic liquid crystalline elastomer films using a fluorinated photoresist and a hard mask process. <i>Journal of Materials Chemistry C</i> , 2017, 5, 12635-12644.	2.7	16
72	Extreme ultraviolet resist materials for sub-7 nm patterning. <i>Chemical Society Reviews</i> , 2017, 46, 4855-4866.	18.7	185

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73	Individually detachable polymer-silicon micro-parts for vaporizable electronics. , 2017, , .		3
74	Recent Progress in EUV Metal Oxide Photoresists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 93-97.	0.1	6
75	Elucidating the patterning mechanism of zirconium-based hybrid photoresists. Journal of Micro/Nanolithography, MEMS, and MOEMS, 2017, 16, 1.	1.0	22
76	Source-based nomenclature for single-strand homopolymers and copolymers (IUPAC) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 622 Td (Rec	0.9	20
77	The development of fluorous photolithographic materials and their applications to achieve flexible organic electronic devices. Flexible and Printed Electronics, 2016, 1, 023001.	1.5	15
78	Ambiguous anti-fouling surfaces: Facile synthesis by light-mediated radical polymerization. Journal of Polymer Science Part A, 2016, 54, 253-262.	2.5	51
79	Positive Tone Nanoparticle Photoresists: New Insight on the Patterning Mechanism. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 509-512.	0.1	7
80	Precise Synthesis of Fluorine-containing Block Copolymers via RAFT. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 705-708.	0.1	6
81	Micrometer-Scale Ordering of Silicon-Containing Block Copolymer Thin Films via High-Temperature Thermal Treatments. ACS Applied Materials & Interfaces, 2016, 8, 9897-9908.	4.0	19
82	Recent progress in nanoparticle photoresists development for EUV lithography. , 2016, , .		9
83	Positive tone oxide nanoparticle EUV (ONE) photoresists. , 2016, , .		4
84	Transient materials from thermally-sensitive polycarbonates and polycarbonate nanocomposites. Polymer, 2016, 101, 59-66.	1.8	19
85	Nanopatterning of Stable Radical Containing Block Copolymers for Highly Ordered Functional Nanomeshes. Macromolecules, 2016, 49, 5884-5892.	2.2	12
86	Kinetics of Block Copolymer Phase Segregation during Sub-millisecond Transient Thermal Annealing. Macromolecules, 2016, 49, 6462-6470.	2.2	23
87	Effects of surface-active block copolymers with oxyethylene and fluoroalkyl side chains on the antifouling performance of silicone-based films. Biofouling, 2016, 32, 81-93.	0.8	43
88	Interface manipulated two-phase nanostructure in a triblock terpolymer with a short middle segment. Polymer Journal, 2016, 48, 533-538.	1.3	3
89	Transient micropackets for silicon dioxide and polymer-based vaporizable electronics. , 2016, , .		6
90	Solubility studies of inorganic-organic hybrid nanoparticle photoresists with different surface functional groups. Nanoscale, 2016, 8, 1338-1343.	2.8	51

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91	Nomenklatura (imenovanje) i grafičko prikazivanje kemijski modificiranih polimera (IUPAC-ove preporuke) Tj ETQq1,1 0.784314 rgBT /Overlock 10 Tf 50 4	0.2	0
92	Block copolymers with stable radical and fluorinated groups by ATRP. MRS Communications, 2015, 5, 441-446.	0.8	6
93	Laser Spike Annealing of DSA Photoresists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 631-634.	0.1	10
94	Oxide Nanoparticle EUV (ONE) Photoresists: Current Understanding of the Unusual Patterning Mechanism. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 515-518.	0.1	21
95	Vertical Oriented Lamellar Formation of Fluorine- and Silicon-containing Block Copolymers without Neutral Layers. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 649-652.	0.1	13
96	Amphiphilic oligopeptides grafted to PDMS-based diblock copolymers for use in antifouling and fouling release coatings. Polymers for Advanced Technologies, 2015, 26, 829-836.	1.6	30
97	Multi-modal graphene polymer interface characterization platform for vaporizable electronics. , 2015, , .		3
98	Alkali Metal Based Micro Combustion Using Graphene Micro-valve Trigger. Journal of Physics: Conference Series, 2015, 660, 012033.	0.3	2
99	Nomenclature and graphic representations for chemically modified polymers (IUPAC) Tj ETQq1 1 0.784314 rgBT /Overlock 10 Tf 50 4	0.9	0
100	Zinc induced polyelectrolyte coacervate bioadhesive and its transition to a self-healing hydrogel. RSC Advances, 2015, 5, 66871-66878.	1.7	78
101	Studying the Mechanism of Hybrid Nanoparticle Photoresists: Effect of Particle Size on Photopatterning. Chemistry of Materials, 2015, 27, 5027-5031.	3.2	73
102	Systematic study of ligand structures of metal oxide EUV nanoparticle photoresists. , 2015, , .		1
103	Studying the mechanism of hybrid nanoparticle EUV photoresists. Proceedings of SPIE, 2015, , .	0.8	0
104	New developments in ligand-stabilized metal oxide nanoparticle photoresists for EUV lithography. Proceedings of SPIE, 2015, , .	0.8	3
105	Design, Synthesis, and Use of Y-Shaped ATRP/NMP Surface Tethered Initiator. ACS Macro Letters, 2015, 4, 606-610.	2.3	17
106	Widely Tunable Morphologies in Block Copolymer Thin Films Through Solvent Vapor Annealing Using Mixtures of Selective Solvents. Advanced Functional Materials, 2015, 25, 3057-3065.	7.8	86
107	Photopatterning of Indomethacin Thin Films: a Solvent-Free Vapor-Deposited Photoresist. ACS Applied Materials & Interfaces, 2015, 7, 23398-23401.	4.0	2
108	Block Copolymers as Antifouling and Fouling Resistant Coatings. , 2015, , 881-924.		1

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109	Understanding of PS- <i>b</i> -PMMA phase segregation under laser-induced millisecond thermal annealing. Proceedings of SPIE, 2015, , .	0.8	4
110	Control of polystyrene- <i>block</i> -poly(methyl methacrylate) directed self-assembly by laser-induced millisecond thermal annealing. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 031205.	1.0	10
111	Supercritical CO <sub>2</sub> -philic nanoparticles suitable for determining the viability of carbon sequestration in shale. Environmental Science: Nano, 2015, 2, 288-296.	2.2	4
112	A glucose sensor via stable immobilization of the GOx enzyme on an organic transistor using a polymer brush. Journal of Polymer Science Part A, 2015, 53, 372-377.	2.5	58
113	Increasing sensitivity of oxide nanoparticle photoresists. , 2014, , .		13
114	Control of PS- <i>b</i> -PMMA directed self-assembly registration by laser induced millisecond thermal annealing. Proceedings of SPIE, 2014, , .	0.8	11
115	Nanopatterning with tailored molecules. , 2014, , .		3
116	Amphiphilic triblock copolymers with PEGylated hydrocarbon structures as environmentally friendly marine antifouling and fouling-release coatings. Biofouling, 2014, 30, 589-604.	0.8	69
117	Thermally induced orientational flipping of cylindrical phase diblock copolymers. Journal of Materials Chemistry C, 2014, 2, 2175-2182.	2.7	20
118	Controlled roughness reduction of patterned resist polymers using laser-induced sub-millisecond heating. Journal of Materials Chemistry C, 2014, 2, 9115-9121.	2.7	5
119	Phase behaviour of PMMA- <i>b</i> -PHEMA with solvents methanol and THF: modelling and comparison to the experiment. Soft Matter, 2014, 10, 6172-6181.	1.2	6
120	Generalized Platform for Antibody Detection using the Antibody Catalyzed Water Oxidation Pathway. Journal of the American Chemical Society, 2014, 136, 1879-1883.	6.6	30
121	C <sub>60</sub> -containing polymers for electron beam lithography. Polymer Bulletin, 2014, 71, 2395-2405.	1.7	7
122	Control of biofouling on reverse osmosis polyamide membranes modified with biocidal nanoparticles and antifouling polymer brushes. Journal of Materials Chemistry B, 2014, 2, 1724.	2.9	164
123	Laser-Induced Sub-millisecond Heating Reveals Distinct Tertiary Ester Cleavage Reaction Pathways in a Photolithographic Resist Polymer. ACS Nano, 2014, 8, 5746-5756.	7.3	23
124	Metal Oxide Nanoparticle Photoresists for EUV Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 663-666.	0.1	46
125	Line width roughness reduction by rational design of photoacid generator for sub-millisecond laser post-exposure bake. , 2014, , .		2
126	The solvent problem: Redissolution of macromolecules in solution-processed organic electronics. Macromolecular Research, 2013, 21, 248-256.	1.0	20



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127	Biodegradability, Cytotoxicity, and Physicochemical Treatability of Two Novel Perfluorooctane Sulfonate-Free Photoacid Generators. <i>Archives of Environmental Contamination and Toxicology</i> , 2013, 64, 187-197.	2.1	8
128	Inkjet printing of fluorinated materials and their application to patterning organic semiconductors. <i>Journal of Materials Chemistry C</i> , 2013, 1, 5647.	2.7	9
129	Responsive and patterned polymer brushes. <i>Journal of Polymer Science, Part B: Polymer Physics</i> , 2013, 51, 1457-1472.	2.4	55
130	A brief guide to polymer nomenclature from IUPAC. <i>Colloid and Polymer Science</i> , 2013, 291, 457-458.	1.0	2
131	A Brief Guide to Polymer Nomenclature. <i>Polymer Degradation and Stability</i> , 2013, 98, 1-2.	2.7	6
132	Early detection of <i>Candida albicans</i> biofilms at porous electrodes. <i>Analytical Biochemistry</i> , 2013, 433, 192-201.	1.1	15
133	Fibronectin conformation regulates the proangiogenic capability of tumor-associated adipogenic stromal cells. <i>Biochimica Et Biophysica Acta - General Subjects</i> , 2013, 1830, 4314-4320.	1.1	35
134	ConfChem Conference on A Virtual Colloquium to Sustain and Celebrate IYC 2011 Initiatives in Global Chemical Education—The Continuing Celebration of IYC 2011: What the IUPAC Polymer Division Is Doing To Keep Things Going. <i>Journal of Chemical Education</i> , 2013, 90, 1559-1560.	1.1	1
135	Improved antifouling properties of polymer membranes using a “layer-by-layer” mediated method. <i>Journal of Materials Chemistry B</i> , 2013, 1, 5651.	2.9	35
136	From surface coatings to polymer nanofilms: lifting off polymer brushes. <i>RSC Advances</i> , 2013, 3, 18482.	1.7	5
137	A Brief Guide to Polymer Nomenclature. <i>Polymer</i> , 2013, 54, 3-4.	1.8	6
138	A Brief Guide to Polymer Nomenclature. <i>Polymer International</i> , 2013, 62, 111.	1.6	1
139	Photo-cleavable anti-fouling polymer brushes: A simple and versatile platform for multicomponent protein patterning. <i>Polymer</i> , 2013, 54, 1762-1767.	1.8	16
140	A brief guide to polymer nomenclature. <i>Reactive and Functional Polymers</i> , 2013, 73, iv-v.	2.0	1
141	Characterization of Polymer Brush Membranes via HF Etch Liftoff Technique. <i>ACS Macro Letters</i> , 2013, 2, 241-245.	2.3	19
142	Orthogonal Patterning of Multiple Biomolecules Using an Organic Fluorinated Resist and Imprint Lithography. <i>Biomacromolecules</i> , 2013, 14, 993-1002.	2.6	16
143	Semi-perfluoroalkyl polyfluorene with varying fluorine content: synthesis and photophysical properties. <i>Polymer Chemistry</i> , 2013, 4, 5291.	1.9	8
144	Biomimetic Polymer Brushes Containing Tethered Acetylcholine Analogs for Protein and Hippocampal Neuronal Cell Patterning. <i>Biomacromolecules</i> , 2013, 14, 529-537.	2.6	45

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145	Oxide nanoparticle EUV resists: toward understanding the mechanism of positive and negative tone patterning. Proceedings of SPIE, 2013, , .	0.8	19
146	Line edge roughness of high deprotection activation energy photoresist by using sub-millisecond post exposure bake. , 2013, , .		4
147	Non-aqueous negative-tone development of inorganic metal oxide nanoparticle photoresists for next generation lithography. Proceedings of SPIE, 2013, , .	0.8	7
148	Nanoparticle Photoresists: Ligand Exchange as a New, Sensitive EUV Patterning Mechanism. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 659-664.	0.1	40
149	Combinatorial Techniques to Efficiently Investigate and Optimize Organic Thin Film Processing and Properties. Molecules, 2013, 18, 4120-4139.	1.7	5
150	Synthesis and characterization of self-assembling block copolymers containing fluorine groups. Proceedings of SPIE, 2012, , .	0.8	0
151	Negative-tone development of photoresists in environmentally friendly silicone fluids. Proceedings of SPIE, 2012, , .	0.8	1
152	Tightly bound ligands for hafnium nanoparticle EUV resists. , 2012, , .		3
153	A brief guide to polymer nomenclature (IUPAC Technical Report). Pure and Applied Chemistry, 2012, 84, 2167-2169.	0.9	48
154	A new inorganic EUV resist with high-etch resistance. Proceedings of SPIE, 2012, , .	0.8	36
155	Synthesis and Characterization of High-Throughput Nanofabricated Poly(4-Hydroxy Styrene) Membranes for <i>In Vitro</i> Models of Barrier Tissue. Tissue Engineering - Part C: Methods, 2012, 18, 667-676.	1.1	11
156	Deprotection reaction kinetics in chemically amplified photoresists determined by sub-millisecond post exposure bake. Proceedings of SPIE, 2012, , .	0.8	1
157	Investigation of acid diffusion during laser spike annealing with systematically designed photoacid generators. Proceedings of SPIE, 2012, , .	0.8	5
158	Nanoparticle photoresists from HfO <sub>2</sub> and ZrO <sub>2</sub> for EUV patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 583-586.	0.1	54
159	Top-down Meets Bottom up: Block Copolymers with Photoreactive Segments. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 17-20.	0.1	4
160	Polymer Brushes as Functional, Patterned Surfaces for Nanobiotechnology. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 53-56.	0.1	9
161	Terminology for aggregation and self-assembly in polymer science (IUPAC Recommendations 2013). Pure and Applied Chemistry, 2012, 85, 463-492.	0.9	21
162	Materials for biosurfaces. Journal of Materials Chemistry, 2012, 22, 19343.	6.7	6

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163	Reconstruction of Surfaces from Mixed Hydrocarbon and PEG Components in Water: Responsive Surfaces Aid Fouling Release. <i>Biomacromolecules</i> , 2012, 13, 1864-1874.	2.6	39
164	Neutron Reflectivity Characterization of the Photoacid Reaction-Diffusion Latent and Developed Images of Molecular Resists for Extreme Ultraviolet Lithography. <i>Langmuir</i> , 2012, 28, 7665-7678.	1.6	13
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